

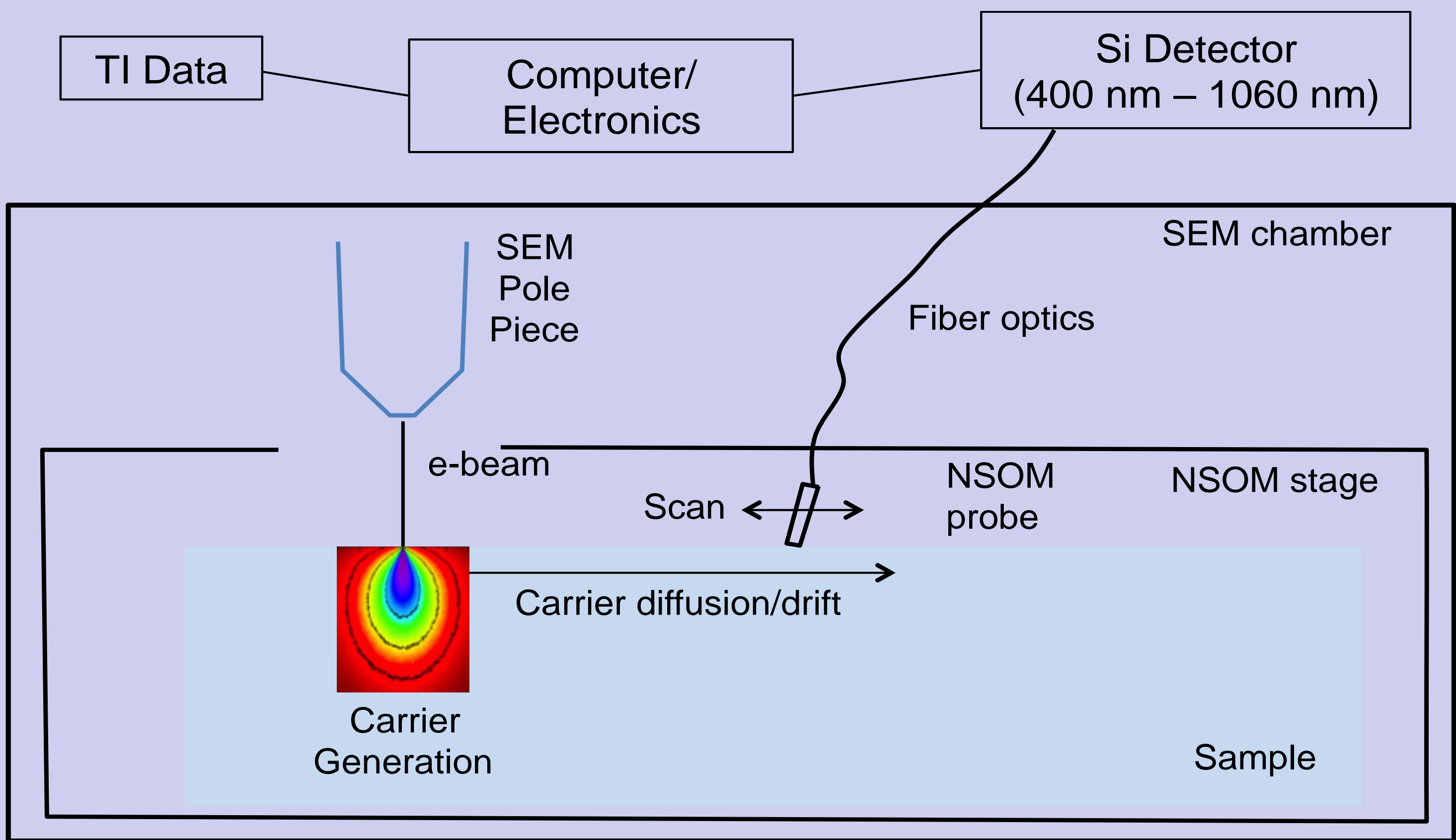
Development of Transport Imaging Technique

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Transport Imaging (TI) is an innovative approach that integrates a scanning electron microscope with a near-field scanning optical microscope. The goal is to “see” the transport of carriers and determine minority carrier diffusion lengths from a single image and map spatial variations in drift and diffusion behavior properties.

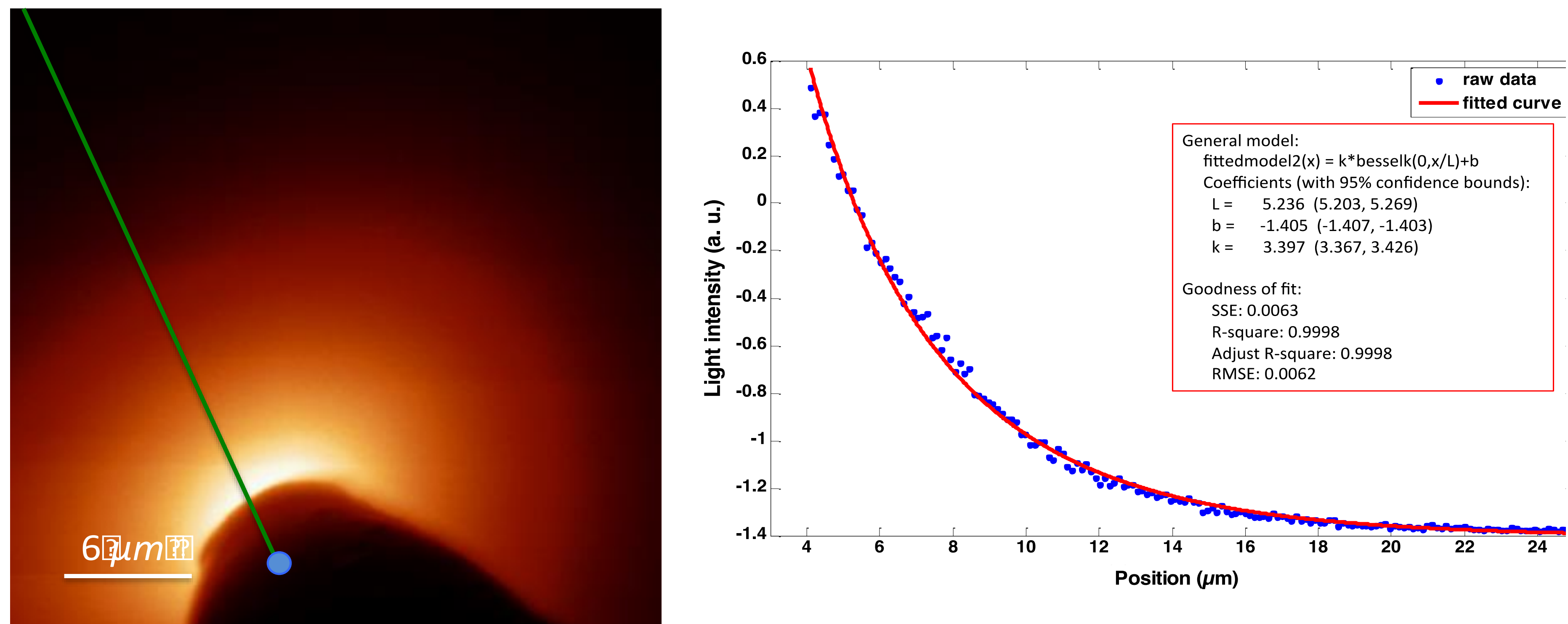
Setup schematic:



Technique advantages:

1. Direct imaging of minority carrier diffusion/drift
2. Generation and detection of recombination at any specific location of interest
3. Direct determination of diffusion length in single films and devices
4. Investigation of carrier kinetics in a wide-range of inhomogeneous mediums involving extended defects, grain boundaries, interfaces, etc.
5. Nanometer-scale resolution

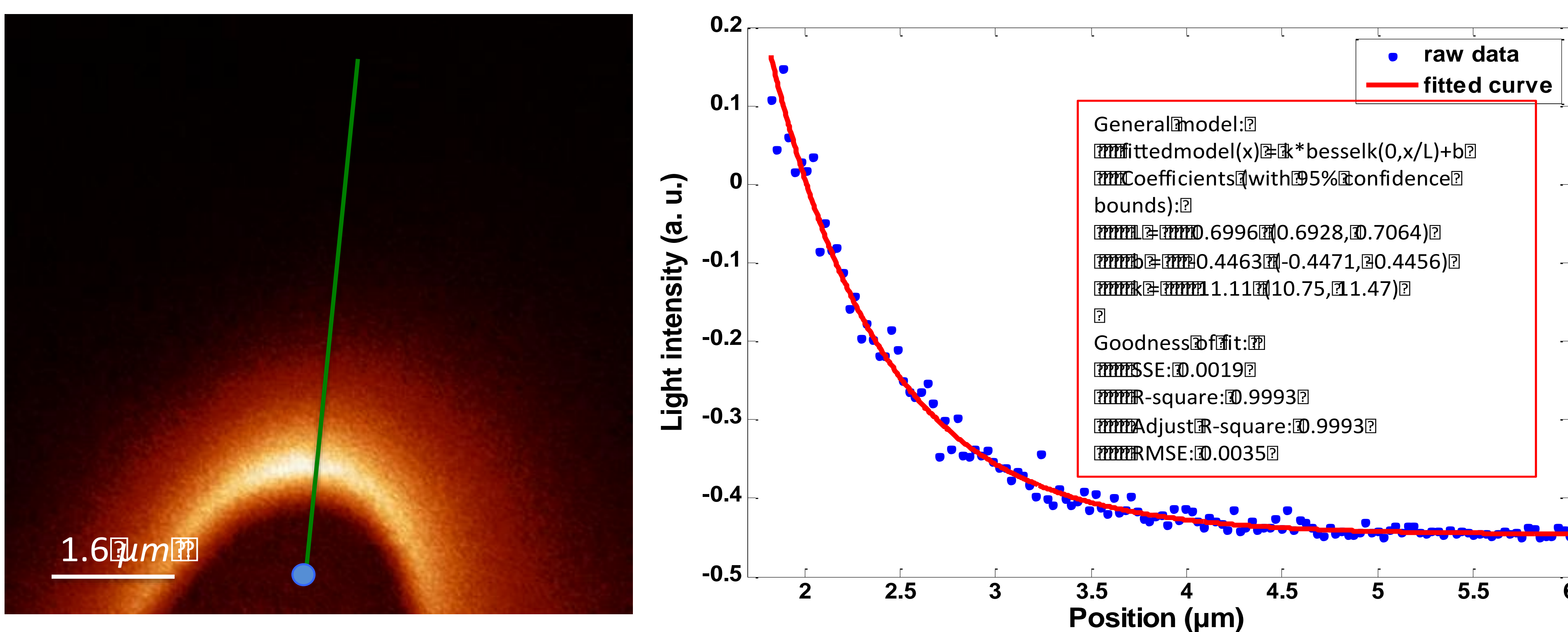
Diffusion length on GaAs



Left) TI image for a GaAs single crystal sample with a 30-nm InGaP cap layer, the blue dot indicates the position of the electron beam (not size); right) fitting linescan curve in Matlab to determine diffusion length

Measurement of diffusion length directly from TI data on single film (no device required)

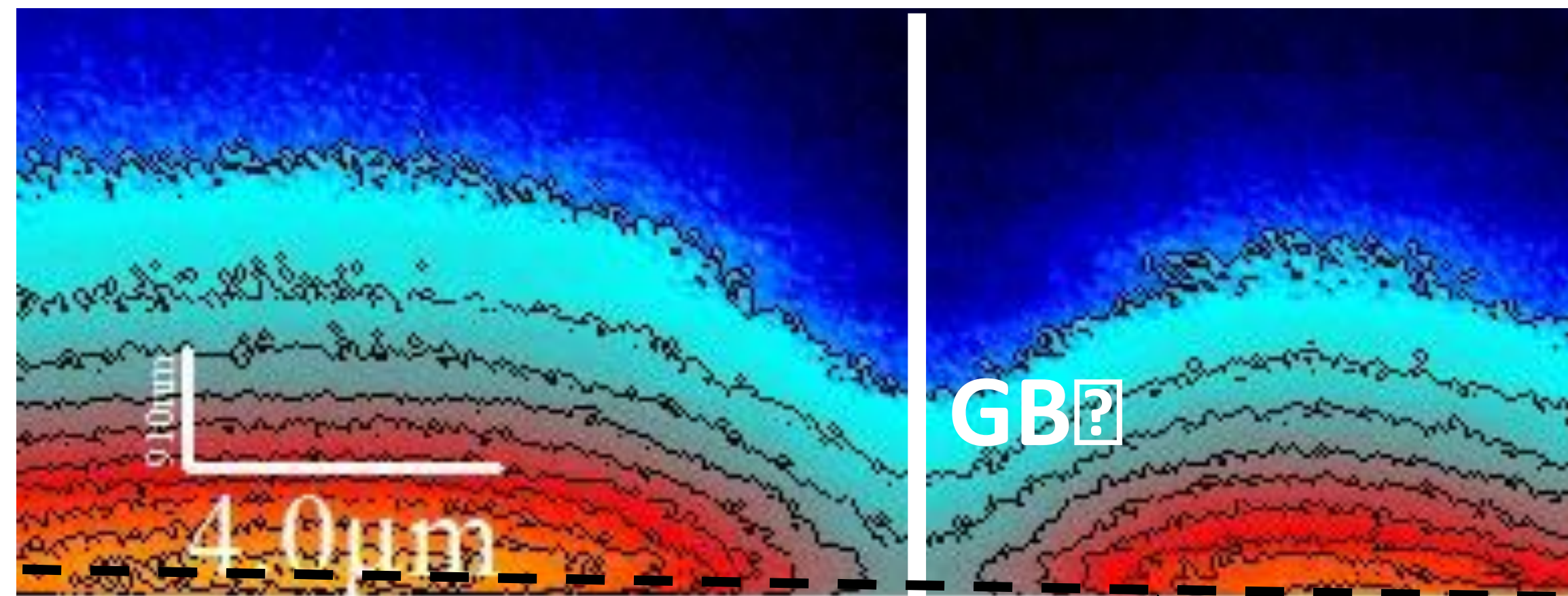
Diffusion length on CdTe



Left) TI data from a CdTe thin film; b) fitting linescan curve in Matlab to determine diffusion length

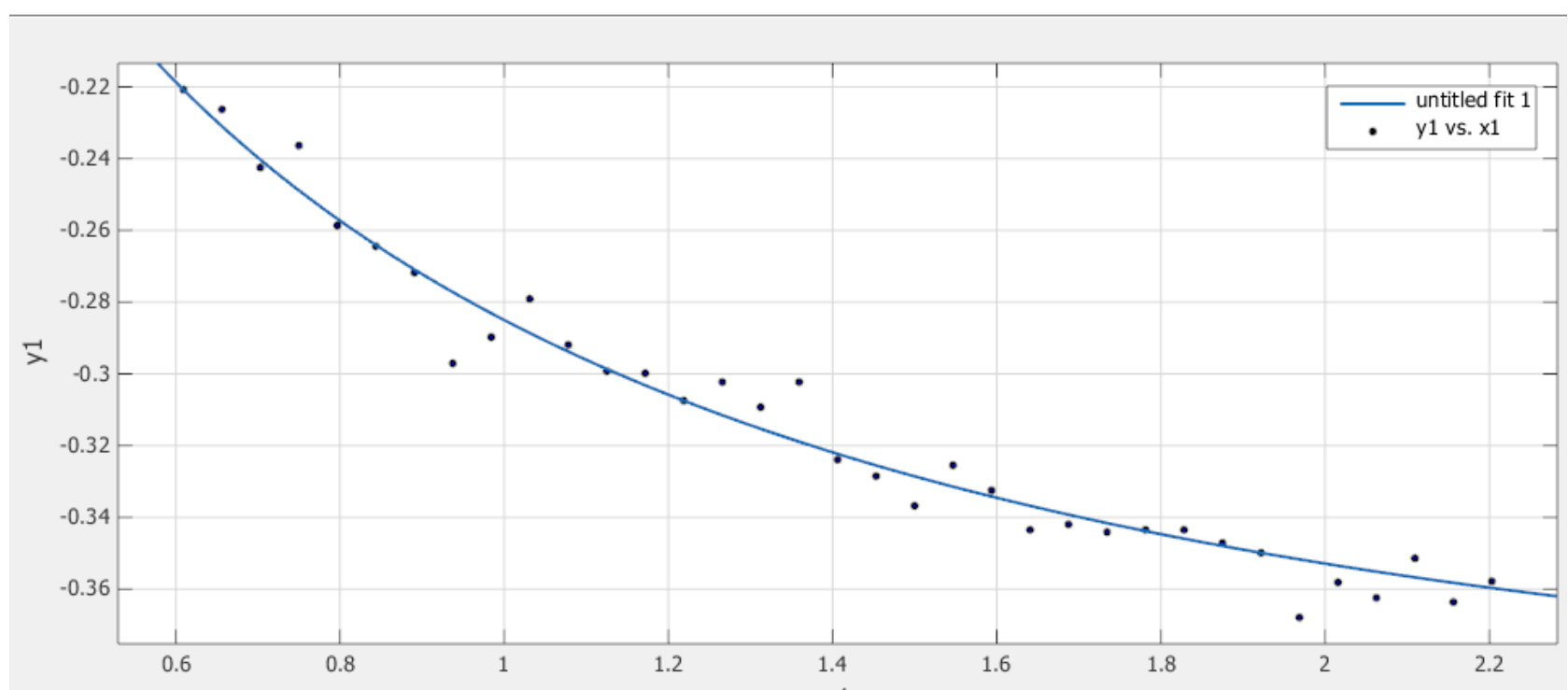
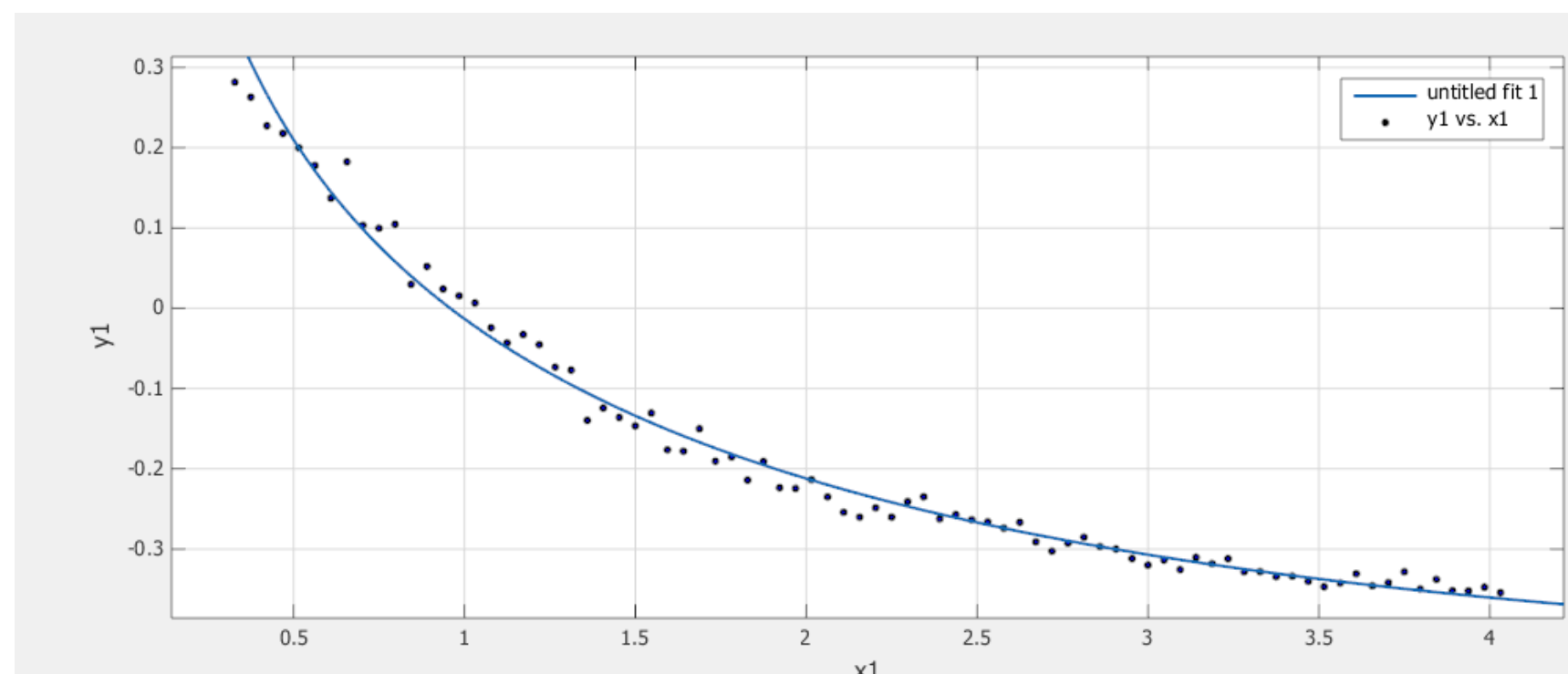
- **First ever TI application on polycrystalline thin film solar cell material**
- **Direct measurement of diffusion length of CdTe**
- **Potential to investigate carrier transport properties in individual grains and grain boundaries**

Effect of boundary on CdTe bicrystal

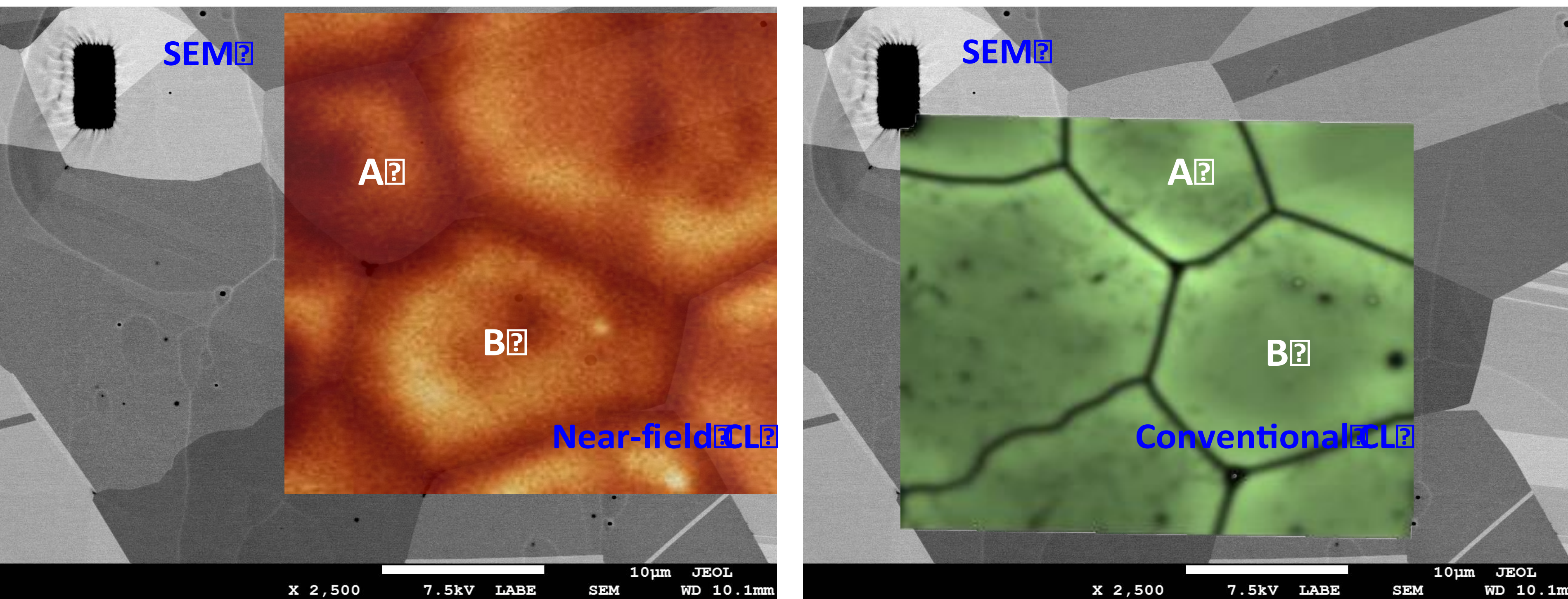


- **Electron beam scanned in a line perpendicular to grain boundary**
- **Enhanced charge carrier recombination at the boundary**
- **Measurement of diffusion length at regions few micrometers apart**

Electron beam



Near-field CL vs. conventional CL of CdTe



Comparison between near-field CL (left) and conventional CL (right) analyses on a CdTe thin film.

- **Near-field probes the recombination signal close to the generation point, conventional CL measures total luminescence plotted at the point of generation**
- **An additional mode of analysis that makes the TI technique more versatile**